Amendments to the Specification

Please replace page 6, lines 3-5 with the following amended paragraph:

(10) The electrical circuit of Item (9), wherein the inorganic particles are fumed silica particles ~~prepared by a vapor deposition method~~.

Please replace page 8, lines 16-18 with the following amended paragraph:

(23) The thin film transistor of Item (22), wherein the inorganic particles are fumed silica particles ~~prepared by a vapor deposition method~~.

Please replace page 13, lines 4-6 with the following amended paragraph:

(46) The method for manufacturing the electrical circuit of Item (45), wherein the inorganic particles are fumed silica particles ~~prepared by a vapor deposition method~~.

Please replace page 18, lines 7-9 with the following amended paragraph:

(69) The method for manufacturing the thin film transistor of Item (68), wherein the inorganic particles are fumed silica particles ~~prepared by a vapor deposition method~~.

Please replace last paragraph bridging pages 34 and 35 with the following amended paragraph:

In the present invention, preferred as inorganic particles are alumina, pseudo boehmite, and colloidal silica, as well as minute silica particles synthesized by a vapor deposition method which are also referred to as fumed silica particles. Of these, most preferred are minute silica particles synthesized by a vapor deposition method (also referred to as fumed silica particles). Also, the surface of the fumed silica particle ~~synthesized by a vapor deposition method~~ may be modified by Al. The content of Al in the Al modified fumed silica particles ~~synthesized by a vapor deposition method~~ is preferably 0.05 to 5 percent by weight based on the weight of silica.

Please replace page 55, lines 6-11 with the following amended paragraph:

After 0.6 kg of AEROSIL 300 (at a primary particle diameter of 7 nm) produced by Nippon Aerosil Co., Ltd. was suction-dispersed into 3 kg of colloidal silica (at a primary particle diameter of 10 - 20 nm, 20 percent aqueous dispersion, produced by Nissan Chemical Industries, Ltd.), AEROSIL 300 being ~~a gas phase method silica~~ fumed silica particles, pure water was added to prepare 7 L of the dispersed liquid. Further, 0.7 L of an aqueous solution containing 27 g of boric acid and 23 g of borax, and 1 g a defoamer (SN381, produced by Sannopco Co.) were added. The resulting mixture was dispersed twice employing a high pressure homogenizer at a pressure of 2.45×10^7 Pa, whereby an aqueous silica-dispersed liquid was prepared. While stirring at 40°C, 1 L of 5 percent aqueous polyvinyl alcohol solution was added to 1 L of the resulting aqueous silica-dispersed liquid, whereby a receptive layer coating liquid composition was prepared.